



# AST-S200T Microscope System

## 2 SPECIFICATIONS

### Camera:

- Cooled InGaAs (900-1700nm)
- Silicon-based option for NIR applications (740nm-1100nm)

### Illumination:

- Epi, optimized Koehler
- Transmitted, optimized sub-stage

### Filters:

- Multi position filter slider sets available based on application

### Aperture/Field Diaphragms:

- Manual adjust

### Magnification:

- 10x-1000x

### Objectives:

- 1x-100x, (1x, 2.5x, 5x, 10x, 20x, 50x, 100x). Greater than 100x objectives are available based on the application

### Turret:

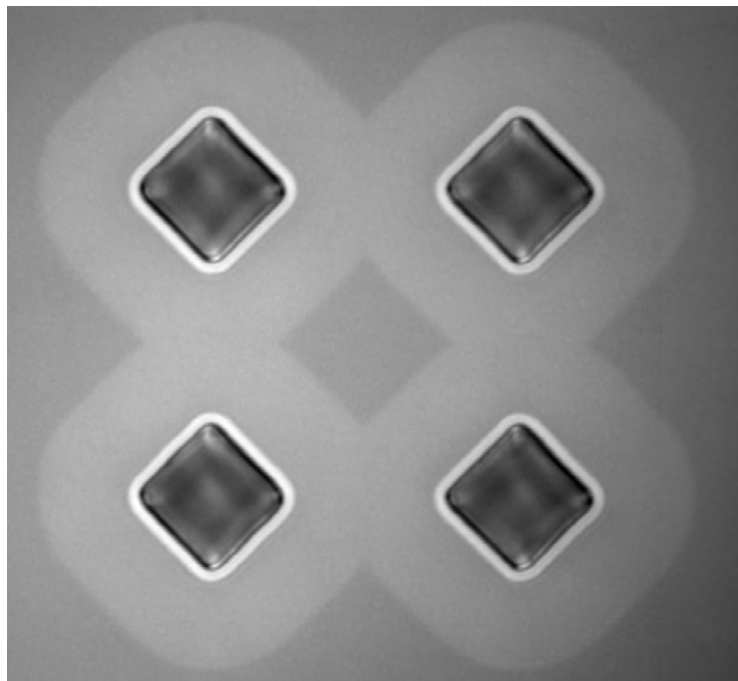
- Manual, optional motorized

### Resolution:

- Submicron optical and digital

### Display:

- Large monitor for live and stored image display



Multi-Layer Alignment

## PLATFORM SPECIFICATIONS

### Stand:

- 8" Microscope stand with coarse/fine Z focus control

### Stage:

- 8" x 8" Stage with coarse/fine manual position control (Other stage sizes available upon request)
- Optional motorized stage with joystick control available

## PROCESS

### In Process:

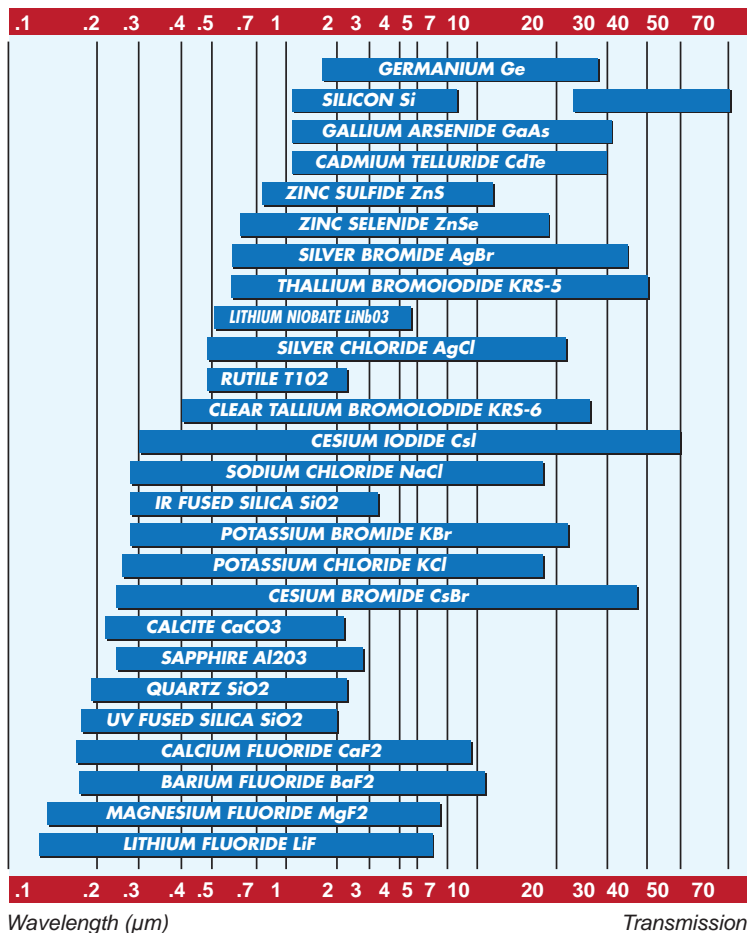
- Verification of critical alignment applications such as: MEMS, wafer bonding, 3D chip stacking, crack/chip inspection metrology

### Post Process:

- Verification, validation, inspection and measurement of critical sub-surface features

### Failure Analysis:

- Process development tool verification, part characterization, qualification and environmental testing



Wavelength (μm)

Transmission